

Applicant(s): Alexander Tregub et al.

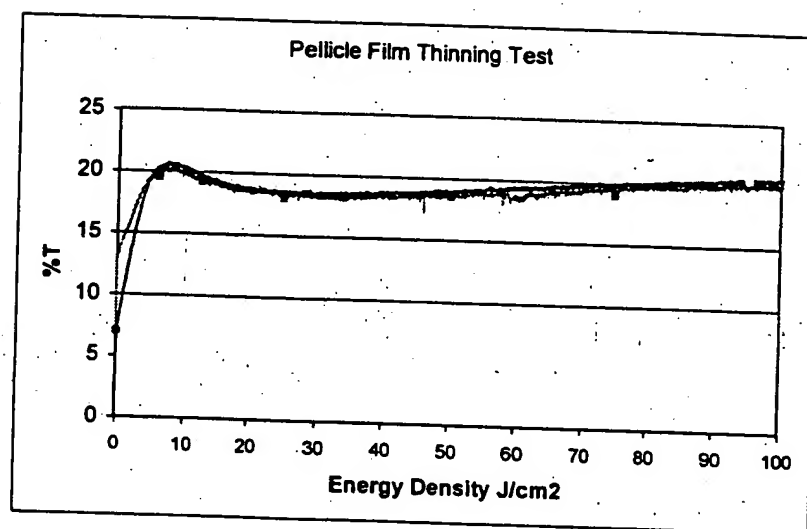
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

Fig.1

Applicant(s): Alexander Tregub et al.

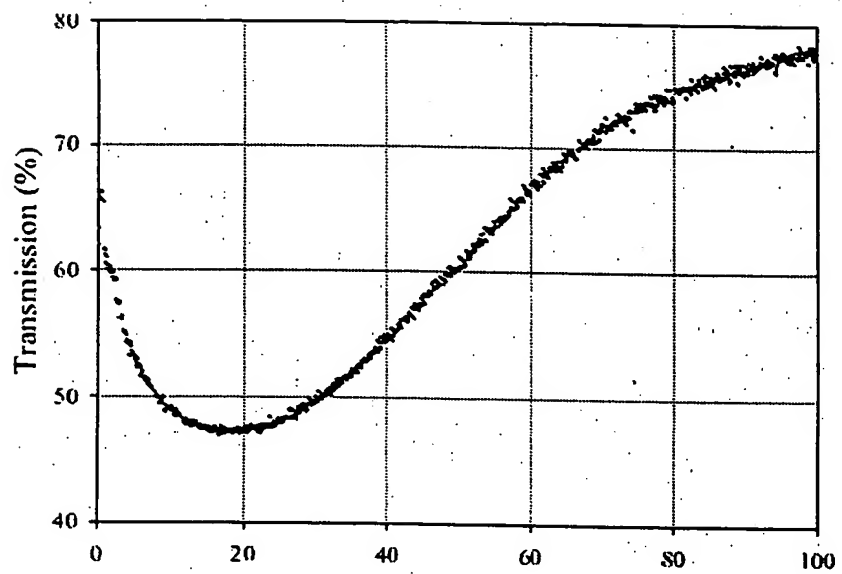
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

Fig. 2

Applicant(s): Alexander Tregub et al.
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

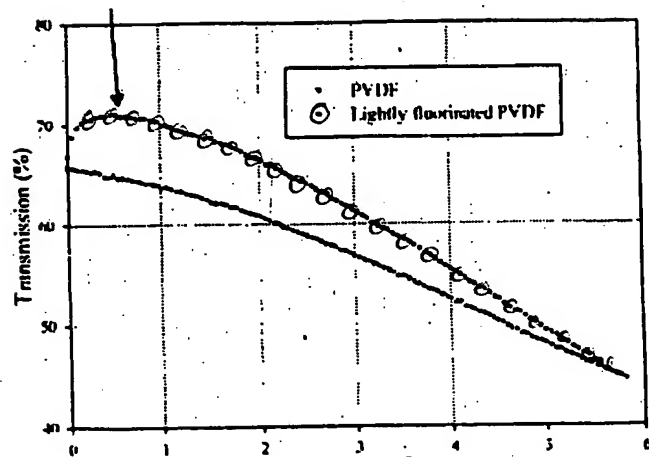


Fig 3

Applicant(s): Alexander Tregub et al.

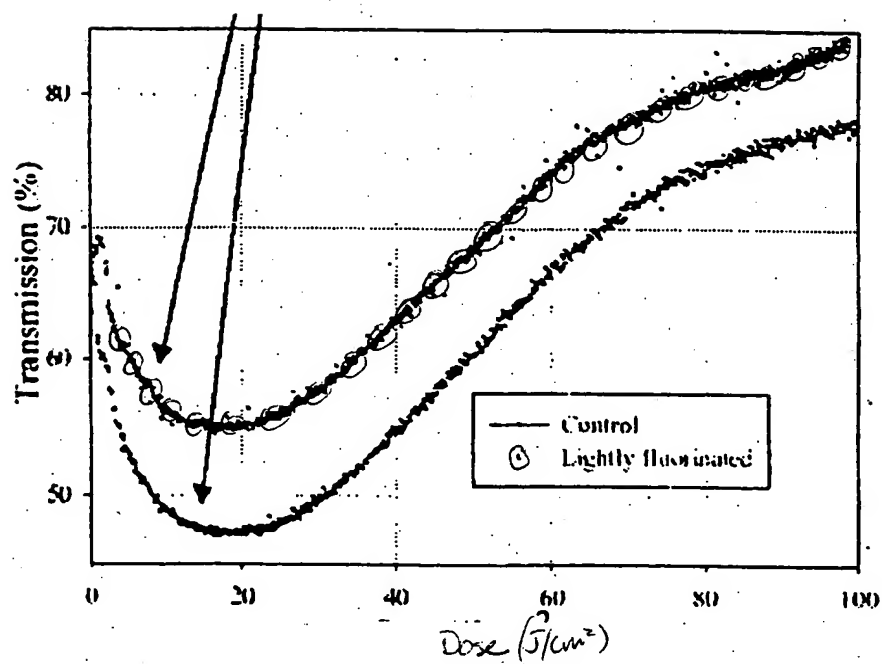
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

FIG. 4

Applicant(s): Alexander Tregub et al.

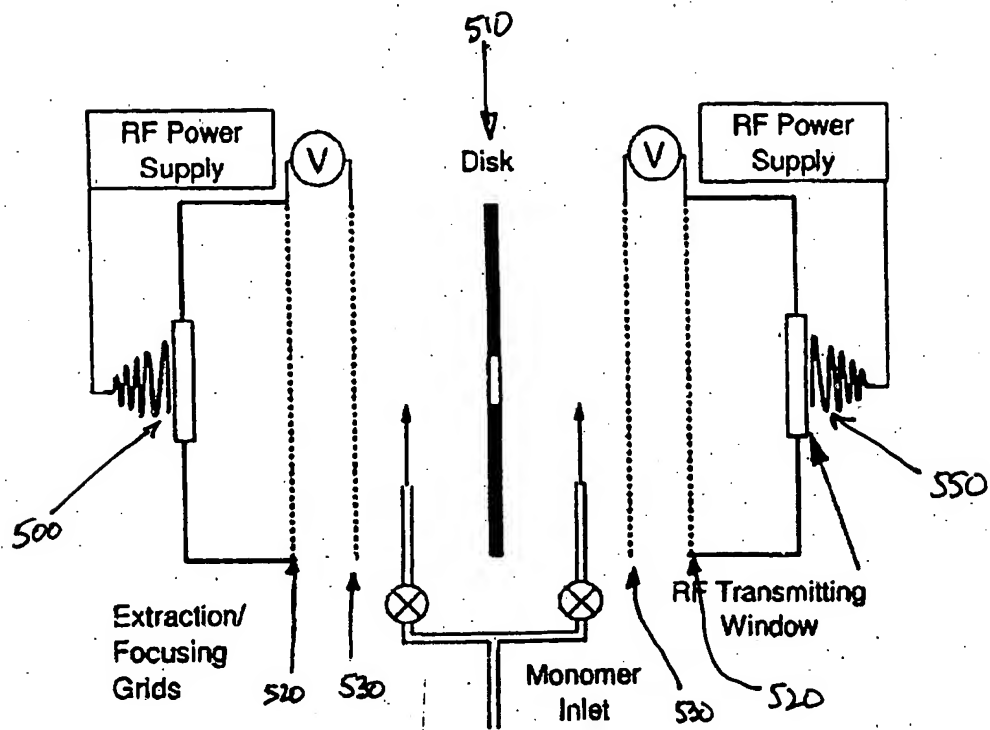
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

FIG. 5

Applicant(s): Alexander Tregub et al.

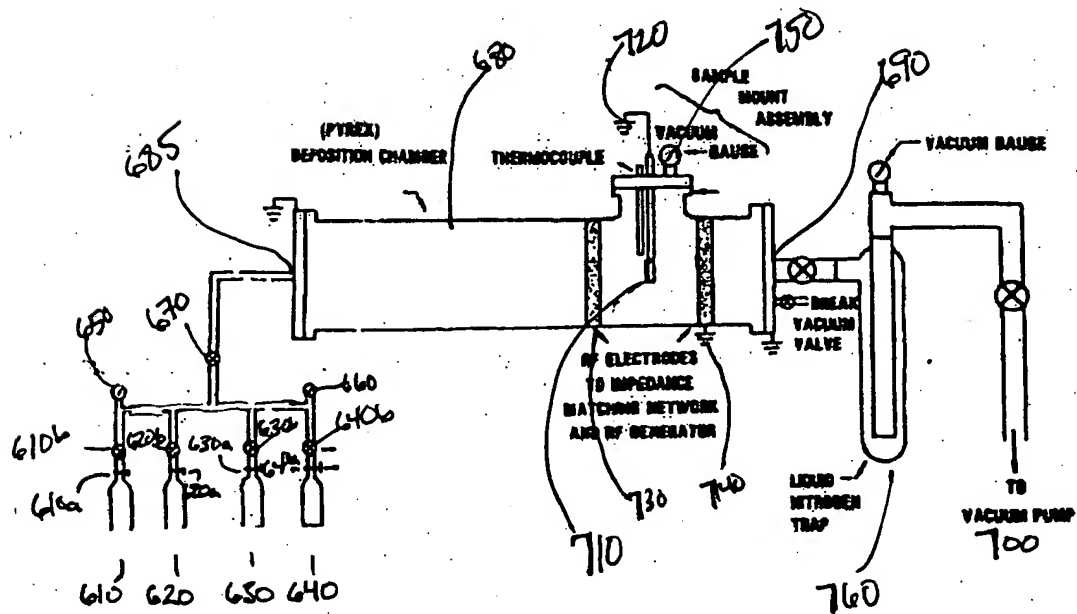
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

FIG. 6

Applicant(s): Alexander Tregub et al.

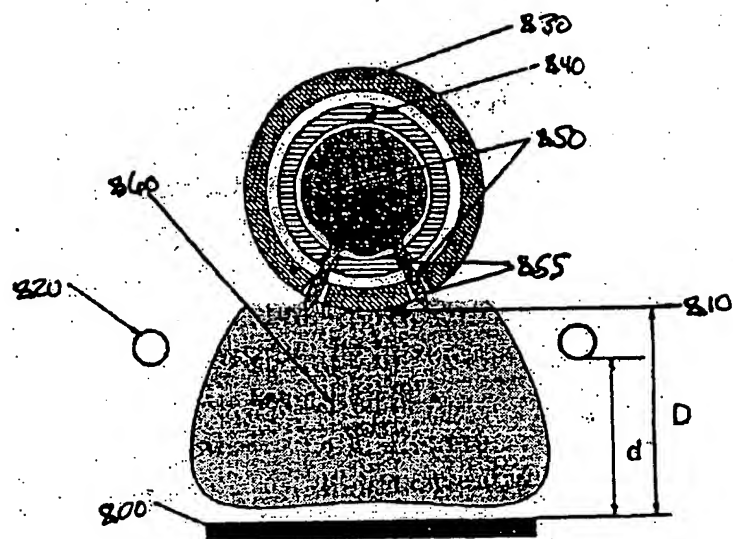
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

FIG. 7

Applicant(s): Alexander Tregub et al.

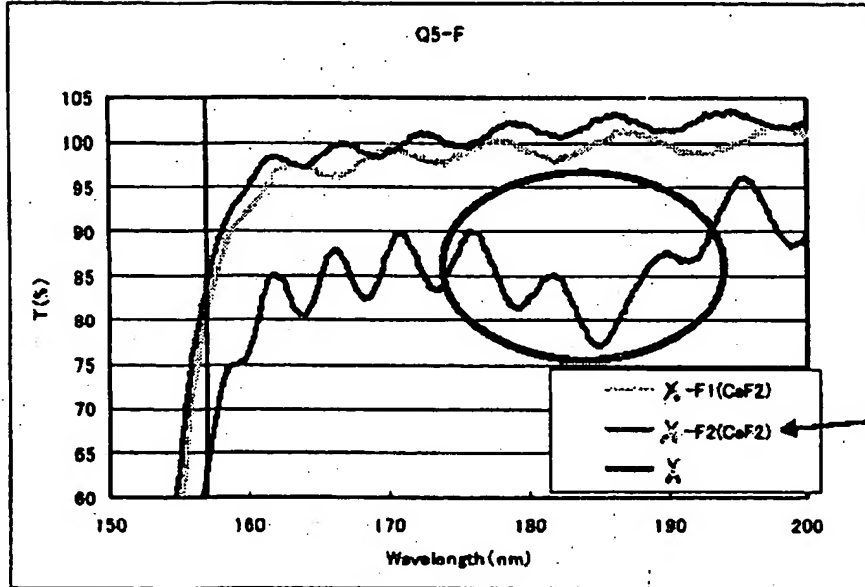
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

FIG. 8

Applicant(s): Alexander Tregub et al.

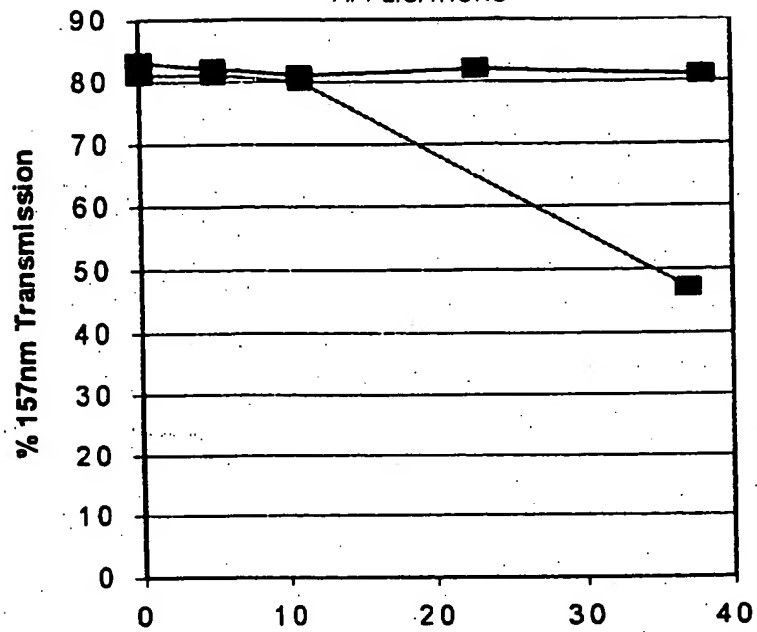
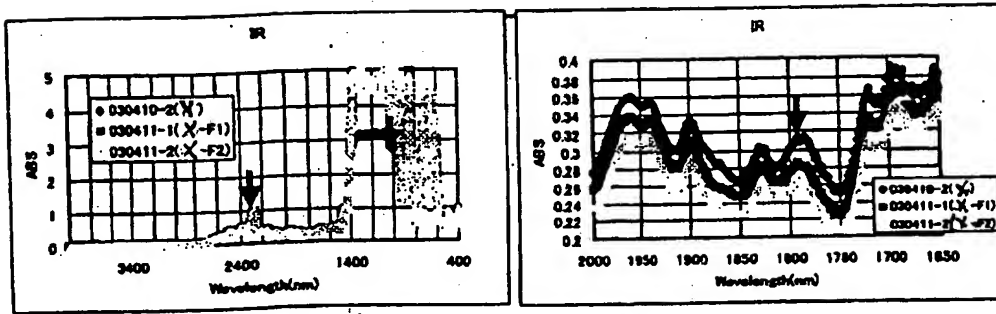
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

Fig. 9

Applicant(s): Alexander Tregub et al.

PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

Peak intensity ratio(1790cm-1 vs 2290cm-1)

	X	X-F1	X-F2
Peak intensity ratio	0.488		0.409

FIG.10